

Schedule by Room (1)

Room	Cap.	Sep. 16 (Mon.)		Sep. 17 (Tue.)		Sep. 18 (Wed.)		
		AM	PM	AM	PM	AM	PM	
TOKI Messe Conference Bldg.	A21	400	9:00 ~ 11:30 15.4 III-V-group nitride crystals	13:00 ~ 17:00 15.4 III-V-group nitride crystals	9:30 ~ 12:00 T16 Organic vs Inorganic Compound Materials, Thin-film Solar Cell Battle Royale	13:30 ~ 17:15 T16 Organic vs Inorganic Compound Materials, Thin-film Solar Cell Battle Royale	9:00 ~ 12:00 23.1 Joint Session N "Informatics"	13:30 ~ 18:50 T29 (Open Symposium) The real thrill of production technologies: What can "Applied Physics" do at the manufacturing site?
	A22	400	9:15 ~ 11:30 13.7 Compound and power devices, process technology and characterization	13:00 ~ 19:00 CS.13 Code-sharing Session of 13.7 & 15.4	9:00 ~ 12:15 KS.2 Quantum Information Engineering Group	13:30 ~ 16:55 T13 Recent trends in research activity related to light, magnetism, and spintronics	9:00 ~ 12:30 21.1 Joint Session K "Wide bandgap oxide semiconductor materials and devices"	13:45 ~ 19:30 21.1 Joint Session K "Wide bandgap oxide semiconductor materials and devices"
	A23	115		13:30 ~ 16:45 T6 Single crystal thin films epitaxially grown on silicon substrates and their device applications	11:00~12:00 Award Ceremony	13:30 ~ 18:25 T26 Recent research progress in properties and applications of carbon nanotubes	9:00 ~ 12:30 13.5 Semiconductor devices/ Interconnect/ Integration technologies	13:30 ~ 19:30 T21 Fundamentals and Latest Technology Trends of Atomic Layer Process (ALP)
	A24	115		13:30 ~ 16:30 NT1 (Open Symposium) A Future Opened by Cutting-edge Semiconductors - Expectations for Applied Physics -	9:00 ~ 11:40 T17 Organic and ionic thermoelectric materials and devices	13:30 ~ 16:25 T17 Organic and ionic thermoelectric materials and devices	9:00 ~ 11:30 13.2 Exploratory Materials, Physical Properties, Devices	13:30 ~ 17:15 23.1 Joint Session N "Informatics"
	A25	75	9:00 ~ 11:45 3.14 Silicon photonics and integrated photonics	13:30 ~ 18:00 3.14 Silicon photonics and integrated photonics		13:30 ~ 14:30 4.8 Optica Special Lecture 14:45 ~ 18:15 4.2 Photonics Devices, Photonic Integrated Circuit and Silicon Photonics	9:00 ~ 12:00 3.6 Laser processing	13:30 ~ 17:45 3.6 Laser processing
	A31	115	9:00 ~ 12:00 17.1 Carbon nanotubes & other nanocarbon materials	13:30 ~ 19:15 17.1 Carbon nanotubes & other nanocarbon materials	10:45 ~ 12:00 4.3 Laser sources and Laser applications	13:30 ~ 17:45 4.3 Laser sources and Laser applications	9:00 ~ 12:00 8.2 Plasma deposition of thin film, plasma etching and surface treatment	13:30 ~ 18:30 8.2 Plasma deposition of thin film, plasma etching and surface treatment
	A32	115		13:30 ~ 17:15 3.1 Basic optics and frontier of optics	9:00 ~ 12:00 3.1 Basic optics and frontier of optics	13:30 ~ 17:00 3.1 Basic optics and frontier of optics	9:00 ~ 12:00 KS.2 Quantum Information Engineering Group	13:30 ~ 18:45 8.5 Plasma phenomena, emerging area of plasmas and their new applications 18:45 ~ 19:00 8.6 Plasma Electronics English Session
	A33	115	9:00 ~ 12:00 FS.1 Focused Session "AI Electronics"	13:30 ~ 18:00 FS.1 Focused Session "AI Electronics"	9:00 ~ 12:00 FS.1 Focused Session "AI Electronics"	13:30 ~ 17:00 FS.1 Focused Session "AI Electronics"	9:00 ~ 11:45 3.11 Nanoscale optical science and near-field optics	13:00 ~ 18:30 3.11 Nanoscale optical science and near-field optics
	A34	115		12:15~13:45 Tutorial (*open to everyone) "Trials towards diversity and inclusion"	9:00 ~ 12:00 4.1 Plasmonics and Nanophotonics	13:00 ~ 17:45 3.10 Photonic structures and phenomena	9:30 ~ 12:00 CS.5 Code-sharing Session of 3.10 & 3.12	13:30 ~ 18:00 3.10 Photonic structures and phenomena
	A35	75	9:00 ~ 12:00 11.1 Fundamental properties	14:00~16:30 Tutorial (*paid session)	9:00 ~ 12:00 4.5 Nanocarbon and 2D Materials	13:30 ~ 16:45 T3 Recent developments in semiconductor radiation detectors	10:00 ~ 12:00 CS.6 Code-sharing Session of 4.5 & 17	13:30 ~ 16:15 CS.6 Code-sharing Session of 4.5 & 17
A36	45	9:30 ~ 12:15 T7 Advanced Technology on the Cyber-Physical System for the Society 5.0	13:30 ~ 17:30 T7 Advanced Technology on the Cyber-Physical System for the Society 5.0			9:00 ~ 10:30 3.13 Optical control devices and optical fibers	13:30 ~ 18:15 T11 Application of Advanced Ion/Electron Microscopy for Future Nanoscale Materials and Devices	
A37	75		13:30 ~ 17:00 CS.2 Code-sharing Session of 3.2 & 4.4	9:00 ~ 11:45 CS.2 Code-sharing Session of 3.2 & 4.4	13:30 ~ 15:00 CS.2 Code-sharing Session of 3.2 & 4.4 15:30 ~ 16:45 16.2 Energy Harvesting	9:00 ~ 12:00 17.2 Graphene	13:30 ~ 16:30 17.2 Graphene	
A41	543	10:00 ~ 11:30 8.7 Plasma Electronics Invited Talk	13:30 ~ 17:30 T18 (Open Symposium) The Frontline of Materials, Processes, and Packaging Technologies Collaborating with State-of-the-Art Logic Semiconductors	10:30 ~ 11:20 NT2 (Open Symposium) Advanced power semiconductor striving in Japan	13:00 ~ 17:25 NT2 (Open Symposium) Advanced power semiconductor striving in Japan	9:00 ~ 12:00 12.5 Organic and hybrid solar cells	13:30 ~ 17:05 T20 The strategic direction of EV shift - Its current status and challenges -	
TOKI Messe Exhibition Hall B	B1	95	9:00 ~ 12:00 13.4 Si processing /Si based thin film / MEMS / Equipment technology	13:00 ~ 17:00 13.4 Si processing /Si based thin film / MEMS / Equipment technology	9:00 ~ 11:00 13.4 Si processing /Si based thin film / MEMS / Equipment technology	13:00 ~ 16:00 13.2 Exploratory Materials, Physical Properties, Devices	9:00 ~ 11:30 13.8 Optical properties and light-emitting devices	13:00 ~ 18:45 13.9 Compound solar cells
	B2	95		13:00 ~ 17:15 13.6 Nanostructures, quantum phenomena, and nano quantum devices	9:00 ~ 11:30 15.7 Crystal characterization, impurities and crystal defects	13:00 ~ 15:30 15.7 Crystal characterization, impurities and crystal defects	9:15 ~ 11:30 15.3 III-V-group epitaxial crystals, Fundamentals of epitaxy	13:00 ~ 18:15 4.6 Terahertz Photonics
	B3	95			9:30 ~ 11:30 6.1 Ferroelectric thin films	13:00 ~ 17:45 6.1 Ferroelectric thin films	10:30 ~ 12:00 6.1 Ferroelectric thin films	13:00 ~ 16:15 CS.7 Code-sharing Session of 6.1 & 13.3 & 13.5
	B4	95	9:00 ~ 12:00 4.1 Plasmonics and Nanophotonics	13:00 ~ 17:00 4.1 Plasmonics and Nanophotonics	9:00 ~ 11:15 6.6 Probe Microscopy	13:00 ~ 18:30 CS.10 Code-sharing Session of 6.6 & 12.2	9:00 ~ 11:30 6.6 Probe Microscopy	
	B5	95			9:45 ~ 11:30 2.5 Radiation-induced phosphors	13:00 ~ 17:30 2.5 Radiation-induced phosphors	9:00 ~ 11:45 11.5 Junction and circuit fabrication process, digital applications	13:00 ~ 17:15 11.4 Analog applications and their related technologies
	B6	95		13:00 ~ 19:30 12.2 Characterization and Materials Physics	9:00 ~ 11:30 12.4 Organic light-emitting devices and organic transistors	13:00 ~ 17:30 12.4 Organic light-emitting devices and organic transistors	9:00 ~ 11:45 12.4 Organic light-emitting devices and organic transistors	13:00 ~ 15:00 12.4 Organic light-emitting devices and organic transistors

Schedule by Room (2)

Room	Cap.	Sep. 19 (Thu.)		Sep. 20 (Fri.)		
		AM	PM	AM	PM	
TOKI Messe Conference Bldg.	A21	400	9:30 ~ 11:50 T28 Research paradigm shift by AI and robotics	13:30 ~ 17:05 T28 Research paradigm shift by AI and robotics	9:00 ~ 11:45 23.1 Joint Session N "Informatics"	13:30 ~ 16:30 23.1 Joint Session N "Informatics"
	A22	400	9:15 ~ 11:45 NT3 (Open Symposium) Create the Future by Yourself - New World Developed by Semiconductors	13:30 ~ 17:30 T2 Earth's limits? Crisis Avoidance with Plasma and Energy Systems in Planetary Boundaries	9:00 ~ 11:45 21.1 Joint Session K "Wide bandgap oxide semiconductor materials and devices"	13:00 ~ 16:30 21.1 Joint Session K "Wide bandgap oxide semiconductor materials and devices"
	A23	115	9:00 ~ 11:55 T23 Advancements in Junction Technologies and Cutting-Edge Si-LSIs: Past, Present, and Future	13:30 ~ 16:25 T23 Advancements in Junction Technologies and Cutting-Edge Si-LSIs: Past, Present, and Future	9:30 ~ 11:50 T27 Vibronics: Energy transport science of vibrations in solid	13:15 ~ 16:05 T27 Vibronics: Energy transport science of vibrations in solid
	A24	115	9:00 ~ 12:00 KS.1 Solid State Quantum Sensor Group	13:30 ~ 17:45 T10 Technological Advances and Future Prospects in Measurement of Organic and Biological Systems by Atomic Force Microscopy	9:00 ~ 11:30 15.4 III-V-group nitride crystals	13:30 ~ 17:00 NT4 (Open Symposium) Linking Future Visions to Gen Z: Creative Networking from JSAP
	A25	75	9:00 ~ 12:00 3.5 Ultrashort-pulse and high-intensity lasers	13:30 ~ 18:00 3.5 Ultrashort-pulse and high-intensity lasers	9:00 ~ 11:45 3.3 Biomedical optics	13:30 ~ 15:15 3.3 Biomedical optics
	A31	115	9:00 ~ 12:00 17.3 Layered materials	13:30 ~ 18:15 17.3 Layered materials	9:00 ~ 12:00 17.3 Layered materials	13:15 ~ 17:00 17.3 Layered materials
	A32	115	9:00 ~ 11:45 3.9 Optical quantum physics and technologies	13:30 ~ 18:15 3.9 Optical quantum physics and technologies	9:00 ~ 12:00 8.1 Plasma production and diagnostics	13:30 ~ 16:30 8.1 Plasma production and diagnostics
	A33	115	9:00 ~ 12:00 CS.4 Code-sharing Session of 3.10 & 3.11	13:30 ~ 18:30 3.11 Nanoscale optical science and near-field optics	9:00 ~ 11:45 8.4 Plasma life sciences	13:30 ~ 17:00 8.4 Plasma life sciences
	A34	115	9:15 ~ 11:30 12.1 Fabrications and Structure Controls	13:30 ~ 18:15 3.8 Terahertz technologies	9:00 ~ 12:00 3.8 Terahertz technologies	13:30 ~ 17:00 3.8 Terahertz technologies
	A35	75	9:00 ~ 12:00 3.12 Semiconductor optical devices	13:30 ~ 17:35 T24 Crystallization and Applications of Thin Film Semiconductors		13:30 ~ 16:00 3.12 Semiconductor optical devices
	A36	45	9:00 ~ 11:00 8.3 Plasma nanotechnology	13:30 ~ 17:00 T1 Human Resource Development and Education Initiatives in Science Education and its Revitalization -Hokuriku /Shinetsu Region-		
	A37	75	9:15 ~ 12:00 3.7 Optical measurement, instrumentation, and sensor	13:30 ~ 17:45 3.7 Optical measurement, instrumentation, and sensor	9:00 ~ 10:30 CS.3 Code-sharing Session of 3.4 & 3.13 10:45 ~ 12:00 3.4 Laser system and materials	13:30 ~ 17:00 3.4 Laser system and materials
	A41	543	9:30 ~ 11:40 T9 Towards social applications of physical reservoir computing using new materials and new principles	13:30 ~ 17:10 T9 Towards social applications of physical reservoir computing using new materials and new principles	9:00 ~ 12:00 CS.8 Code-sharing Session of 6.2 & KS.1	13:30 ~ 15:45 KS.1 Solid State Quantum Sensor Group
	TOKI Messe Exhibition Hall B	B1	95		13:00 ~ 17:15 13.3 Insulator technology	
B2		95	9:15 ~ 11:30 15.3 III-V-group epitaxial crystals, Fundamentals of epitaxy	13:00 ~ 16:45 3.6 Laser processing		
B3		95	9:00 ~ 11:30 6.2 Carbon-based thin films	13:00 ~ 19:15 6.2 Carbon-based thin films	9:30 ~ 11:30 6.3 Oxide electronics	13:00 ~ 17:00 6.3 Oxide electronics
B4		95				
B5		95	9:30 ~ 11:45 15.5 Group IV crystals and alloys	13:00 ~ 17:15 15.5 Group IV crystals and alloys		
B6		95	9:00 ~ 11:30 12.3 Functional Materials and Novel Devices	13:00 ~ 18:15 12.3 Functional Materials and Novel Devices	9:00 ~ 11:30 12.3 Functional Materials and Novel Devices	13:00 ~ 15:30 12.3 Functional Materials and Novel Devices

Schedule by Room (3)

Room	Cap.	Sep. 16 (Mon.)		Sep. 17 (Tue.)		Sep. 18 (Wed.)		
		AM	PM	AM	PM	AM	PM	
Hotel Nikko Niigata	C31	72	9:00 ~ 11:30 6.4 Thin films and New materials	13:00 ~ 18:00 6.4 Thin films and New materials	9:00 ~ 12:00 11.1 Fundamental properties	13:00 ~ 18:45 12.7 Biomedical Engineering and Biochips	9:00 ~ 11:30 12.7 Biomedical Engineering and Biochips	13:00 ~ 18:30 12.7 Biomedical Engineering and Biochips
	C32	72	9:00 ~ 11:45 16.1 Fundamental properties, evaluation, process and devices in disordered materials	13:15 ~ 16:45 16.1 Fundamental properties, evaluation, process and devices in disordered materials	9:00 ~ 11:30 3.14 Silicon photonics and integrated photonics	13:00 ~ 16:45 12.6 Nanobiotechnology	9:00 ~ 11:30 12.1 Fabrications and Structure Controls	13:00 ~ 16:30 12.6 Nanobiotechnology
	C41	240	9:00 ~ 12:00 T14 New direction of perovskite solar cells	13:30 ~ 18:30 T14 New direction of perovskite solar cells	9:30 ~ 10:30 8.8 Plasma Electronics Division Award Speech 11:00 ~ 11:45 8.7 Plasma Electronics Invited Talk	13:30 ~ 19:00 T12 Plasma direct bonding technology for next-generation semiconductor and new device manufacturing	9:00 ~ 10:45 15.6 Group IV Compound Semiconductors (SiC)	13:30 ~ 17:00 T22 Interdisciplinary Expansion of Interfacial Nano-Electrochemistry -From Advanced Semiconductors to Biosciences-
	C42	285	10:00 ~ 11:50 T15 Frontier of flexible and stretchable electronics	13:30 ~ 18:25 T15 Frontier of flexible and stretchable electronics	9:00 ~ 11:30 15.4 III-V-group nitride crystals	13:30 ~ 18:30 T25 Emergence of Novel Functions in Nitride and III/V Group Compound Semiconductor Nanostructures	9:00 ~ 12:30 15.4 III-V-group nitride crystals	13:30 ~ 17:15 T8 2D materials and their integrated circuit and electronic device applications
	C43	64	9:00 ~ 12:00 7.1 X-ray technologies	13:00 ~ 16:00 1.5 Instrumentation, measurement and Metrology	9:30 ~ 11:45 1.3 Novel technologies and interdisciplinary engineering	13:00 ~ 17:30 1.6 Ultrasonics	9:00 ~ 11:30 1.1 Interdisciplinary and General Physics	13:00 ~ 17:45 1.4 Energy conversion, storage, resources and environment
	C301	80		13:00 ~ 18:30 9.2 Nanoparticles, Nanowires and Nanosheets	9:00 ~ 11:30 6.4 Thin films and New materials	13:30 ~ 16:45 9.4 Thermoelectric conversion	9:00 ~ 11:30 CS.11 Code-sharing Session of 9.4 & M	13:00 ~ 16:15 9.1 Dielectrics, ferroelectrics
	C302	180		13:00 ~ 18:15 13.5 Semiconductor devices/ Interconnect/ Integration technologies	9:00 ~ 12:00 13.8 Optical properties and light-emitting devices	13:30 ~ 17:30 T19 Materials for Green & Sustainable Semiconductor Manufacturing	10:00 ~ 11:35 T4 Crossover between Photonic Computing and AI: From New Trends to Applications	13:00 ~ 17:20 T4 Crossover between Photonic Computing and AI: From New Trends to Applications
Bandai-jima Bldg.	D61	95	9:00 ~ 11:15 10.2 Fundamental and exploratory device technologies for spin	13:00 ~ 16:45 10.2 Fundamental and exploratory device technologies for spin	9:00 ~ 11:30 10.3 Spin devices, magnetic memories and storages	13:30 ~ 17:15 6.3 Oxide electronics		13:00 ~ 18:45 10.4 Spintronics in semiconductor, topological material, superconductor, and multiferroics
	D62	75	10:00 ~ 11:30 2.5 Radiation-induced phosphors	13:00 ~ 17:45 2.5 Radiation-induced phosphors	10:00 ~ 11:45 2.4 Medical application	13:30 ~ 16:00 7.3 Micro/Nano patterning and fabrication	10:00 ~ 11:45 2.4 Medical application	13:30 ~ 18:15 CS.1 Code-sharing Session of 2.3 & 7.4
	D63	49		13:00 ~ 17:45 CS.9 Code-sharing Session of 6.5 & 7.5	10:00 ~ 11:30 7.2 Applications and technologies of electron beams	13:00 ~ 17:15 7.2 Applications and technologies of electron beams		13:00 ~ 18:00 12.1 Fabrications and Structure Controls
TOKI Messe Exhibition Hall A	P		[13:30-15:30] 7 Beam Technology and Nanofabrication 8.2 Plasma deposition of thin film, plasma etching and surface treatment 8.5 Plasma phenomena, emerging area of plasmas and their new applications 8.6 Plasma Electronics English Session 12.1 Fabrications and Structure Controls 13.2 Exploratory Materials, Physical Properties, Devices	[09:30-11:30] 17 Nanocarbon and Two-Dimensional Materials		[13:30-15:30] 6.4 Thin films and New materials 6.5 Surface Physics, Vacuum 11 Superconductivity 23 Joint Session N "Informatics"	[09:30-11:30] 3.1 Basic optics and frontier of optics 3.5 Ultrashort-pulse and high-intensity lasers 3.9 Optical quantum physics and technologies 3.12 Semiconductor optical devices 12.3 Functional Materials and Novel Devices	[13:30-15:30] 2 Ionizing Radiation 6.3 Oxide electronics 6.6 Probe Microscopy 12.2 Characterization and Materials Physics 22 Joint Session M "Phonon Engineering" FS Focused Session "AI Electronics"
			[16:00-18:00] 1 Interdisciplinary Physics and Related Areas of Science and Technology KS Sessions organized by JSAP's Professional Group			[16:00-18:00] 13.4 Si processing /Si based thin film / MEMS / Equipment technology 13.5 Semiconductor devices/ Interconnect/ Integration technologies 13.8 Optical properties and light-emitting devices	13.7 Compound and power devices, process technology and characterization 15.4 III-V-group nitride crystals	[16:00-18:00] 6.1 Ferroelectric thin films 12.4 Organic light-emitting devices and organic transistors 12.5 Organic and hybrid solar cells 15.5 Group IV crystals and alloys 15.6 Group IV Compound Semiconductors (SiC) 15.7 Crystal characterization, impurities and crystal defects

Schedule by Room (4)

Room	Cap.	Sep. 19 (Thu.)		Sep. 20 (Fri.)		
		AM	PM	AM	PM	
Hotel Nikko Niigata	C31	72	9:00 ~ 10:30 11.1 Fundamental properties 10:30 ~ 12:00 11.3 Critical Current, Superconducting Power Applications	13:30 ~ 16:15 11.2 Thin and thick superconducting films, coated conductors and film crystal growth		13:00 ~ 14:30 3.7 Optical measurement, instrumentation, and sensor
	C32	72	9:00 ~ 11:30 CS.12 Code-sharing Session of 12.6 & 12.7	13:00 ~ 16:15 3.3 Biomedical optics	9:00 ~ 11:30 16.3 Bulk, thin-film and other silicon-based solar cells	13:00 ~ 16:00 16.3 Bulk, thin-film and other silicon-based solar cells
	C41	240	9:00 ~ 11:45 13.7 Compound and power devices, process technology and characterization	13:00 ~ 19:30 13.7 Compound and power devices, process technology and characterization		
	C42	285	9:00 ~ 11:30 15.4 III-V-group nitride crystals	13:00 ~ 17:15 15.4 III-V-group nitride crystals	9:00 ~ 12:15 T5 Space photonics for the new space age	13:30 ~ 15:00 15.4 III-V-group nitride crystals
	C43	64	9:00 ~ 10:15 1.2 Education	13:00 ~ 18:00 4.7 Quantum Optics, Nonlinear Optics and Structured Optics	10:00 ~ 11:30 4.7 Quantum Optics, Nonlinear Optics and Structured Optics	13:00 ~ 16:00 13.1 Fundamental properties, surface and interface, and simulations of Si related materials
	C301	80	9:00 ~ 11:00 10.5 Application of magnetic field	13:30 ~ 17:15 9.5 New functional materials and new phenomena	9:00 ~ 11:30 3.5 Ultrashort-pulse and high-intensity lasers	13:00 ~ 16:30 3.5 Ultrashort-pulse and high-intensity lasers
	C302	180	9:00 ~ 12:00 12.5 Organic and hybrid solar cells	13:00 ~ 17:00 12.5 Organic and hybrid solar cells	9:00 ~ 12:00 12.5 Organic and hybrid solar cells	13:00 ~ 16:00 12.5 Organic and hybrid solar cells
Bandai-jima Bldg.	D61	95	9:00 ~ 12:00 2.1 Detection Devices	13:00 ~ 18:00 2.1 Detection Devices	9:00 ~ 11:30 10.1 Emerging materials in spintronics and magnetics (including fabrication and characterization methodologies)	13:00 ~ 17:00 10.1 Emerging materials in spintronics and magnetics (including fabrication and characterization methodologies)
	D62	75	9:00 ~ 11:30 22.1 Joint Session M "Phonon Engineering"	13:00 ~ 18:00 22.1 Joint Session M "Phonon Engineering"	9:00 ~ 12:00 2.2 Radiation physics fundamentals & applications, radiation generators, new technology	13:00 ~ 16:45 15.1 Bulk crystal growth
	D63	49	9:00 ~ 11:30 9.3 Nanoelectronics	13:00 ~ 15:15 9.3 Nanoelectronics		
TOKI Messe Exhibition Hall A	P		[09:30-11:30] 3.2 Information photonics and image engineering 3.3 Biomedical optics 3.4 Laser system and materials 3.6 Laser processing 3.8 Terahertz technologies 3.13 Optical control devices and optical fibers 3.14 Silicon photonics and integrated photonics 4 JSAP-Optica Joint Symposia 2024	[13:30-15:30] 3.10 Photonic structures and phenomena 8.1 Plasma production and diagnostics 8.3 Plasma nanotechnology 8.4 Plasma life sciences 21 Joint Session K "Wide bandgap oxide semiconductor materials and devices"	[09:30-11:30] 3.7 Optical measurement, instrumentation, and sensor 3.11 Nanoscale optical science and near-field optics 12.6 Nanobiotechnology 12.7 Biomedical Engineering and Biochips 13.1 Fundamental properties, surface and interface, and simulations of Si related materials 13.3 Insulator technology 15.1 Bulk crystal growth	[13:30-15:30] 6.2 Carbon-based thin films 9 Applied Materials Science
			[16:00-18:00] 10 Spintronics and Magnetics 13.9 Compound solar cells 15.2 II-VI and related compounds 15.3 III-V-group epitaxial crystals, Fundamentals of epitaxy 16 Amorphous and Microcrystalline Materials			